

L Number	Hits	Search Text	DB	Time stamp
1	466	CHEN-COMING-.in. WU-JUAN-YUAN-.in. WU-J-Y-.in. LUR-WATER-.in. LUR-W-.in.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/26 12:13
2	16681	430/5,311,313,314,316,317.ccls. 438/296,424,427,692,697.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/26 12:13
3	757	(active near region) near2 small\$2	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/26 14:03
4	767	(active near region) near2 larg\$2	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/26 12:14
5	14272	sti! (shallow adj trench adj isolation)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/26 12:15
6	84039	trench	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/26 12:15
7	23	partial adj reverse adj2 (mask active photoresist)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/26 13:40
8	60	((active near region) near2 small\$2 ) with ((active near region) near2 larg\$2 )	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/26 12:17
9	1597867	sio sio2 "sio.sub.2" oxide dioxide	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/26 12:17
10	22	(430/5,311,313,314,316,317.ccls. 438/296,424,427,692,697.ccls.) and ((active near region) near2 small\$2 ) and ((active near region) near2 larg\$2 )	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/26 12:25
11	23693	trench with (sio sio2 "sio.sub.2" oxide dioxide)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/26 12:25
12	34	((((active near region) near2 small\$2 ) with ((active near region) near2 larg\$2 )) and (trench with (sio sio2 "sio.sub.2" oxide dioxide)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/26 12:25
13	17	((((active near region) near2 small\$2 ) with ((active near region) near2 larg\$2 )) same (trench with (sio sio2 "sio.sub.2" oxide dioxide)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/26 12:26
14	17	((((active near region) near2 small\$2 ) with ((active near region) near2 larg\$2 )) and (trench with (sio sio2 "sio.sub.2" oxide dioxide))) not (((active near region) near2 small\$2 ) with ((active near region) near2 larg\$2 )) same (trench with (sio sio2 "sio.sub.2" oxide dioxide)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/26 12:27
15	26	((((active near region) near2 small\$2 ) with ((active near region) near2 larg\$2 )) not (((active near region) near2 small\$2 ) with ((active near region) near2 larg\$2 )) and (trench with (sio sio2 "sio.sub.2" oxide dioxide)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/26 13:21
16	23	((active near region) near2 larg\$2 ) same (sti! (shallow adj trench adj isolation) )	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/26 13:22

17	1546	hpcvd hdpcvd hdp-cvd	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/26 13:24
18	2749	((high adj density adj plasma) (high adj density) hdp) adj ((chemical adj vapor adj deposit\$5) cvd)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/26 13:38
19	1423	((hpcvd hdpcvd hdp-cvd ) (((high adj density adj plasma) (high adj density) hdp) adj ((chemical adj vapor adj deposit\$5) cvd) )) with (sio sio2 "sio.sub.2" oxide dioxide)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/26 13:39
20	418	((hpcvd hdpcvd hdp-cvd ) (((high adj density adj plasma) (high adj density) hdp) adj ((chemical adj vapor adj deposit\$5) cvd) )) with (sio sio2 "sio.sub.2" oxide dioxide)) with trench	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/26 13:46
22	1	((((hpcvd hdpcvd hdp-cvd ) (((high adj density adj plasma) (high adj density) hdp) adj ((chemical adj vapor adj deposit\$5) cvd) )) with (sio sio2 "sio.sub.2" oxide dioxide)) with trench) same (partial with reverse with (mask active photoresist) )	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/26 13:46
23	4	((hpcvd hdpcvd hdp-cvd ) (((high adj density adj plasma) (high adj density) hdp) adj ((chemical adj vapor adj deposit\$5) cvd) )) with (sio sio2 "sio.sub.2" oxide dioxide)) same (partial with reverse with (mask active photoresist) )	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/26 13:46
21	61	partial with reverse with (mask active photoresist)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/26 13:46
25	216	(active near region) near2 wide	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/26 14:04
26	22	(active near region) near2 dense	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/26 14:05
27	1	((active near region) near2 wide) and ((active near region) near2 dense)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/26 14:04
28	341	(active near region) near2 narrow	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/26 14:06
29	40	((active near region) near2 wide) same ((active near region) near2 narrow)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/26 14:06
30	49697	planariz\$5 planaris\$5	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/26 14:11
31	48556	cmp (((chemical\$3 adj mechanical\$3) (chemical\$3-mechanical\$3)) adj polish\$3) chemical\$3-mechanical\$3-polish\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/26 14:12
32	251052	polish\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/26 14:12

33	283713	(planariz\$5 planaris\$5 ) (cmp (((chemical\$3 adj mechanical\$3) (chemical\$3-mechanical\$3)) adj polish\$3) chemical\$3-mechanical\$3-polish\$3 ) polish\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/26 14:12
34	1769	((active near region) near2 small\$2 ) ((active near region) near2 larg\$2 ) ((active near region) near2 wide) ((active near region) near2 narrow)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/26 14:13
35	23	((planariz\$5 planaris\$5 ) (cmp (((chemical\$3 adj mechanical\$3) (chemical\$3-mechanical\$3)) adj polish\$3) chemical\$3-mechanical\$3-polish\$3 ) polish\$3) same ((active near region) near2 small\$2 ) ((active near region) near2 larg\$2 ) ((active near region) near2 wide) ((active near region) near2 narrow)) same (sti! (shallow adj trench adj isolation) )	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/26 14:14
36	144	((planariz\$5 planaris\$5 ) (cmp (((chemical\$3 adj mechanical\$3) (chemical\$3-mechanical\$3)) adj polish\$3) chemical\$3-mechanical\$3-polish\$3 ) polish\$3) and ((active near region) near2 small\$2 ) ((active near region) near2 larg\$2 ) ((active near region) near2 wide) ((active near region) near2 narrow)) and (sti! (shallow adj trench adj isolation) )	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/26 14:14
37	121	((planariz\$5 planaris\$5 ) (cmp (((chemical\$3 adj mechanical\$3) (chemical\$3-mechanical\$3)) adj polish\$3) chemical\$3-mechanical\$3-polish\$3 ) polish\$3) and ((active near region) near2 small\$2 ) ((active near region) near2 larg\$2 ) ((active near region) near2 wide) ((active near region) near2 narrow)) and (sti! (shallow adj trench adj isolation) )) not (((planariz\$5 planaris\$5 ) (cmp (((chemical\$3 adj mechanical\$3) (chemical\$3-mechanical\$3)) adj polish\$3) chemical\$3-mechanical\$3-polish\$3 ) polish\$3) same ((active near region) near2 small\$2 ) ((active near region) near2 larg\$2 ) ((active near region) near2 wide) ((active near region) near2 narrow)) same (sti! (shallow adj trench adj isolation) ))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/26 14:27
38	10	("5728621" or ("5459096" or ("6326309") or ("6001740") or ("5880007"))).PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/26 14:38
39	0	us-588007-\$.did. and (partial with reverse with (mask active photoresist) )	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/07/26 14:38